

Supporting information:

Corrosion stability of NASICON-based membranes against aqueous solutions: case study for sodium iodine batteries

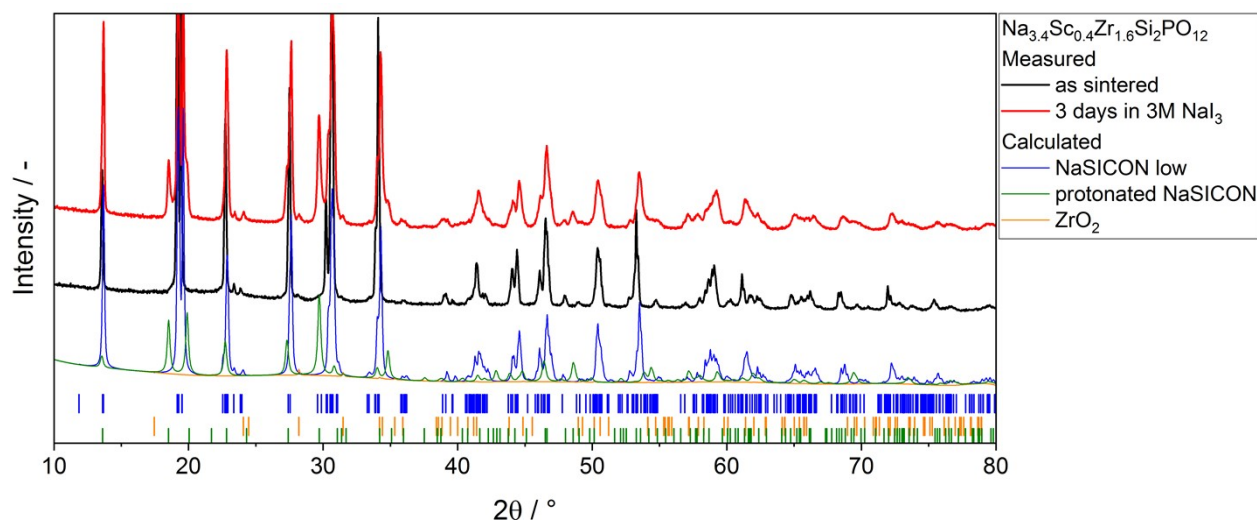


Figure S1: XRD patterns of $\text{Na}_{3.4}\text{Sc}_{0.4}\text{Zr}_{1.6}\text{Si}_2\text{PO}_{12}$ (NSZSiP3.4) as sintered (black) and after 3 days of exposure to 3M NaI_3 solution at 100 °C (red).

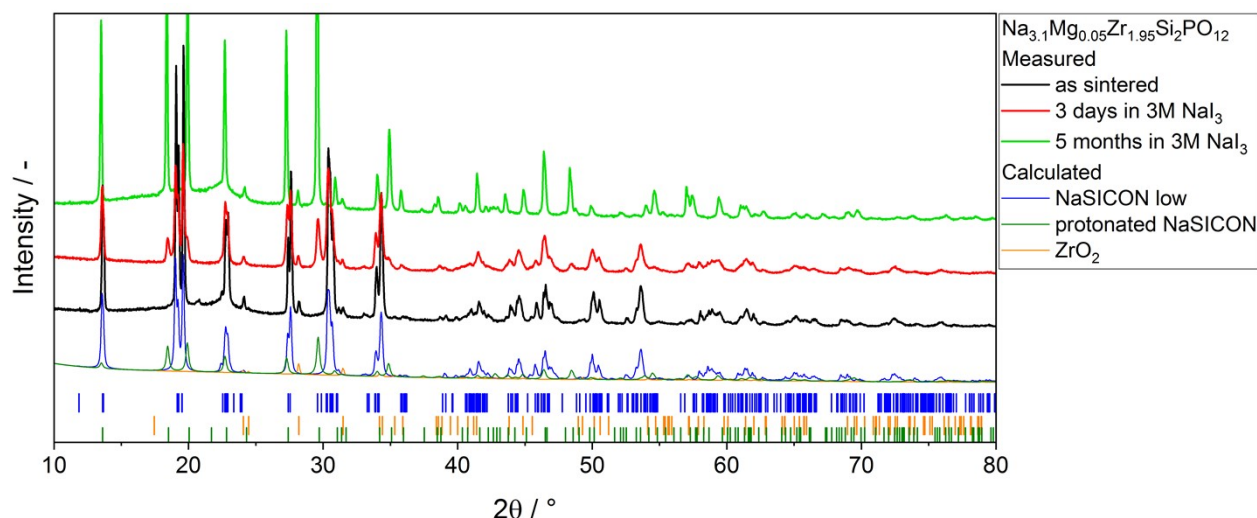


Figure S2: XRD patterns of $\text{Na}_{3.1}\text{Mg}_{0.05}\text{Zr}_{1.95}\text{Si}_2\text{PO}_{12}$ (NMZSiP3.1) as sintered (black), after 3 days (red) and after 5 months (light green) of exposure to 3M NaI_3 solution at 100 °C.

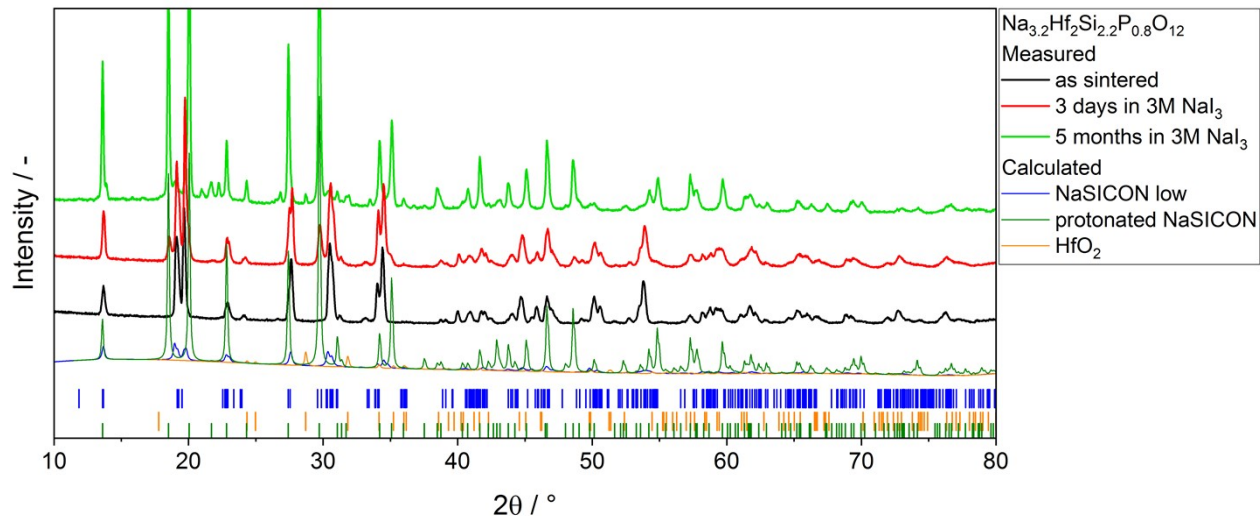


Figure S3: XRD patterns of $\text{Na}_{3.2}\text{Hf}_2\text{Si}_{2.2}\text{P}_{0.8}\text{O}_{12}$ (NHSiP3.2) as sintered (black), after 3 days (red) and after 5 months (light green) of exposure to 3M NaI_3 solution at 100 °C.

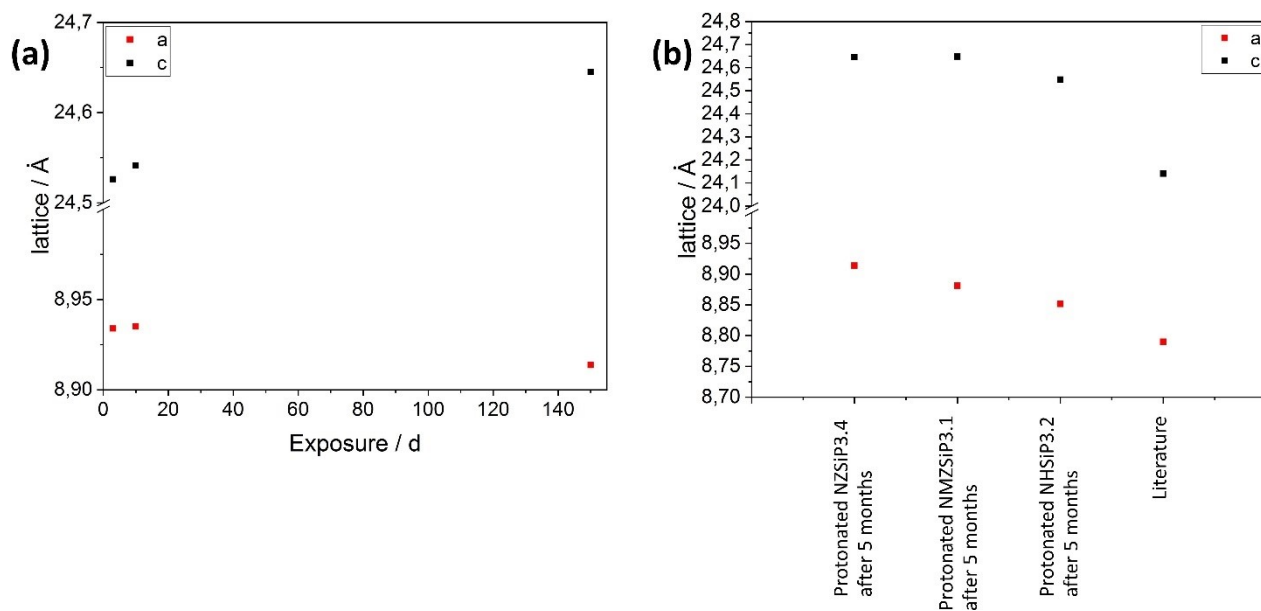


Figure S4: a) Lattice parameters of the protonated NZSiP3.4 as a function of exposure time to 3M NaI_3 at 100 °C. b) Lattice parameters of the protonated phase in the NZSiP3.4, NMZSiP3.1 and NHSiP3.2 in comparison to a non-protonated NaSiCON material.

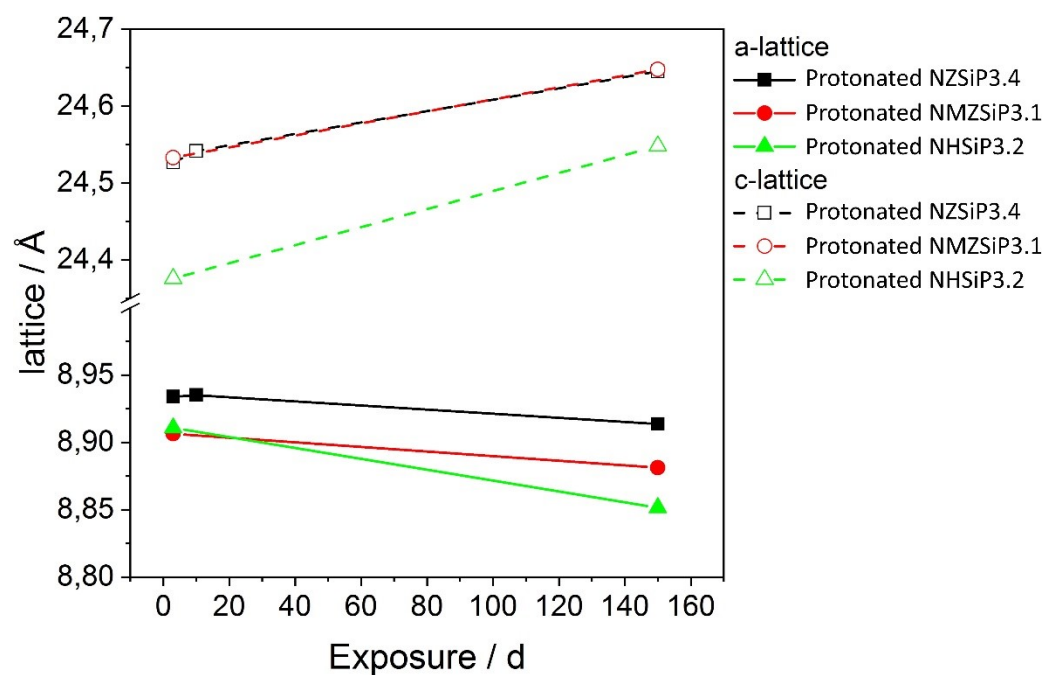


Figure S5: Lattice parameters of the protonated phase in the NZSiP3.4, NMZSiP3.1 and NHSiP3.2 as a function of exposure time to 3M NaI₃ at 100 °C. (Lines are guide to the eye only.)

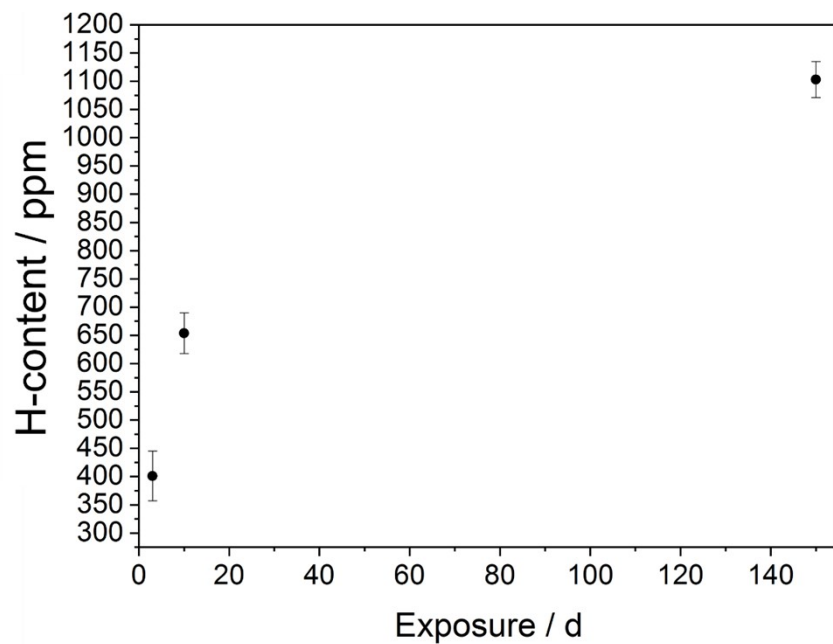


Figure S6: Hydrogen content in the NZSiP3.4 samples after exposure to 3M NaI₃ at 100 °C for 3 days, 10 days and 5 months.

Table S1: Summary of the phase compositions of the investigated powders as-sintered and after exposure to the respective solutions after Rietveld analysis with the ICSD data sets 38096 (NaSICON low), 202279 (basis for protonated NaSICON-Model), 81696 (NaSICON high), 18190 (ZrO₂) and 27313 (HfO₂) as reference.

sample name	phase no.	Phase Name	space group	a (Å)	b (Å)	c (Å)	beta(°)	wt.% Rietveld
NZSiP3.4 as-sintered	1	NaSICON low	C 1 2/c 1	15.738	9.099	9.208	124.273	100
NZSiP3.4 after 7 days in sat. NaI	1	NaSICON low	C 1 2/c 1	15.738	9.099	9.206	124.298	98
	2	protonated NaSICON	R-3c	8.913	-	24.552	-	< 3
NZSiP3.4 after 3 days in 3M NaI sol.	1	protonated NaSICON	R-3c	8.928	-	24.515	-	5
	2	NaSICON low	C 1 2/c 1	15.74	9.1	9.204	124.312	95
NZSiP3.4 after 3 days in 3M NaI sol. at pH=1.29	1	NaSICON low	C 1 2/c 1	15.735	9.099	9.2	124.297	90
	2	protonated NaSICON	R-3c	8.931	-	24.533	-	10
NZSiP3.4 after 3 days in 3M NaI3	1	NaSICON low	C 1 2/c 1	15.736	9.098	9.198	124.304	82
	2	protonated NaSICON	R-3c	8.934	-	24.526	-	18
NZSiP3.4 after 10 days in 3M NaI3	1	protonated NaSICON	R-3c	8.935	-	24.542	-	22
	2	NaSICON low	C 1 2/c 1	15.73	9.096	9.2	124.276	78
NZSiP3.4 after 5 months in 3M NaI3	1	protonated NaSICON	R-3c	8.914	-	24.645	-	100
NZSiP3.4 after 5 months in 3M NaI3 + 14 days in saturated NaI sol.	1	protonated NaSICON	R-3c	8.913	-	24.645	-	100
NScZSiP3.4 as-sintered	1	NaSICON low	C 1 2/c 1	15.716	9.077	9.185	124.483	99
	2	Zirconium-oxide	P 1 21/c 1	5.144	5.21	5.311	99.22	< 3
NScZSiP3.4 after 3 days in 3M NaI3	1	NaSICON low	C 1 2/c 1	15.672	9.06	9.193	124.205	74
	2	protonated NaSICON	R-3c	8.924	-	24.409	-	26
	3	Zirconium-oxide	P 1 21/c 1	5.14422	5.21	5.311	99.22	< 3
NMZSiP3.1 as-sintered	1	NaSICON low	C 1 2/c 1	15.649	9.053	9.221	123.728	98
	2	Zirconium-oxide	P 1 21/c 1	5.144	5.21	5.311	99.22	< 3
NMZSiP3.1 after 3 days in 3M NaI3	1	NaSICON low	C 1 2/c 1	15.639	9.052	9.23	123.647	75
	2	protonated NaSICON	R-3c	8.906	-	24.533	-	23
	3	Zirconium-oxide	P 1 21/c 1	5.144	5.21	5.311	99.22	< 3
NMZSiP3.1 after 5	1	protonated NaSICON	R-3c	8.881	-	24.648	-	98

months in 3M NaI3	2	Zirconium-oxide	P 1 21/c 1	5.144	5.21	5.311	99.22	< 3
NHSiP3.2 as-sintered	1	NaSICON low	C 1 2/c 1	15.595	9.019	9.219	123.683	100
NHZSiP3.2 after 3 days in 3M NaI3	1	NaSICON low	C 1 2/c 1	15.57	9.01	9.217	123.57	75
	2	protonated NaSICON	R-3c	8.911	-	24.376	-	25
NHZSiP3.2 after 5 months in 3M NaI3	1	NaSICON low	C 1 2/c 1	15.466	9.018	9.262	123.113	13
	2	protonated NaSICON	R-3c	8.852		24.548		86
	3	Hafnium-oxide	P 1 21/c 1	5.044	5.091	5.308	98.713	< 3
NZSiP3.0 as-sintered	1	Zirconium-oxide	P 1 21/c 1	5.144	5.21	5.311	99.22	3
	2	NaSICON low	C 1 2/c 1	15.634	9.044	9.224	123.649	97
NZSiP3.0 after 10 days in 3M NaI3	1	NaSICON low	C 1 2/c 1	15.601	9.037	9.239	123.502	48
	2	Zirconium-oxide	P 1 21/c 1	5.144	5.21	5.311	99.22	4
	3	protonated NaSICON	R-3c	8.903	-	24.527	-	49
NZSiP3.0sub as- sintered	1	Zirconium-oxide	P 1 21/c 1	5.144	5.21	5.311	99.22	4
	2	NaSICON low	C 1 2/c 1	15.679	9.072	9.231	123.894	96
NZSiP3.0sub after 10 days in 3M NaI3	1	Zirconium-oxide	P 1 21/c 1	5.144	5.21	5.311	99.22	4
	2	NaSICON low	C 1 2/c 1	15.661	9.071	9.224	123.755	89
	3	protonated NaSICON	R-3c	8.913	-	24.589	-	8
NZSiP1.0 as-sintered	1	NaSICON high	R-3c	8.802	-	22.868	-	100
NZSiP1.0 after 5 months in 3M NaI3	1	protonated NaSICON	R-3c	8.922	-	24.648	-	5
	2	NaSICON high	R-3c	8.808	-	22.775	-	95

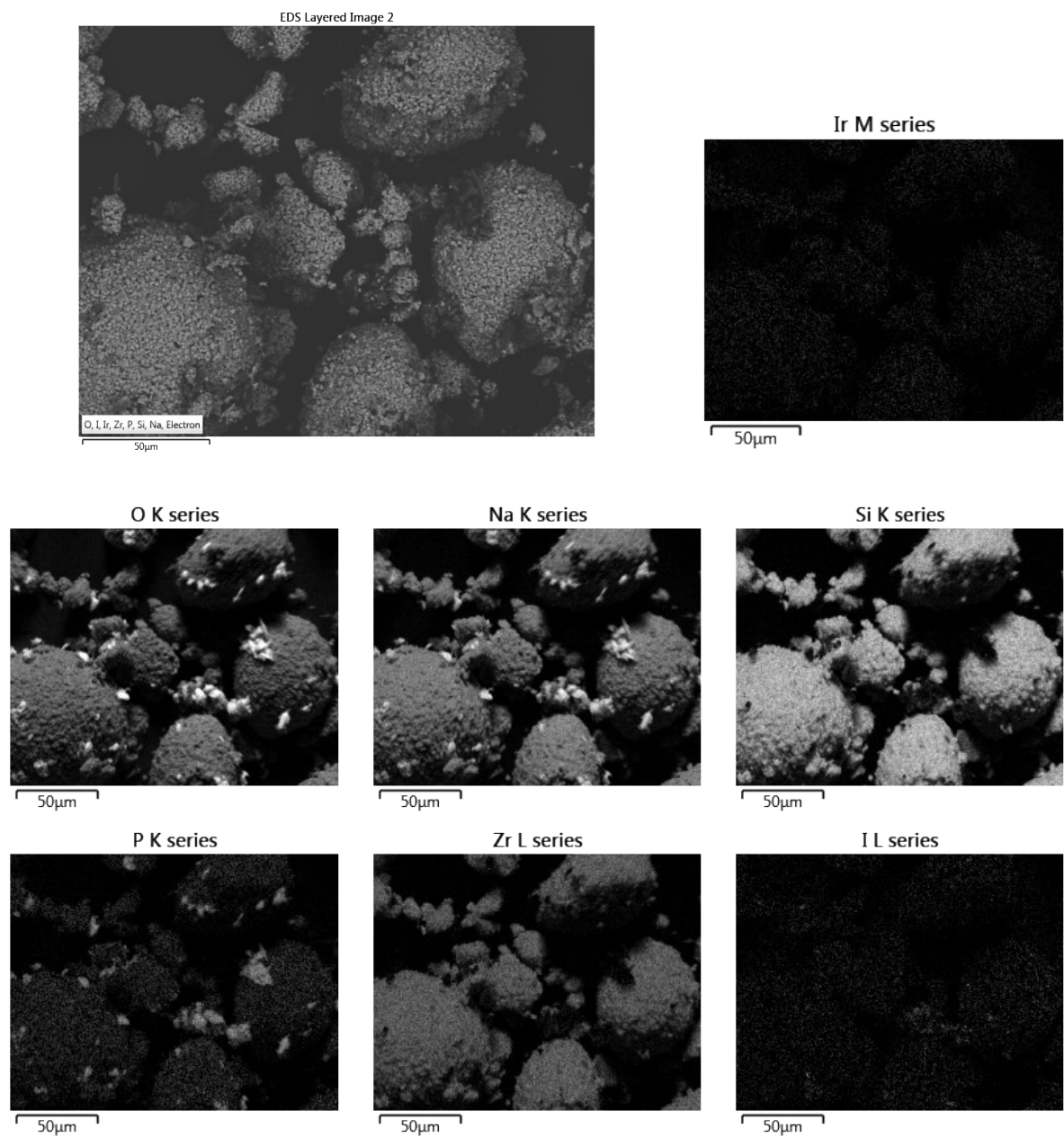


Figure S7: EDS images of sintered NaSICON powder after 3 days of exposure to 3M NaI₃ solution, measured on Ir-waver.

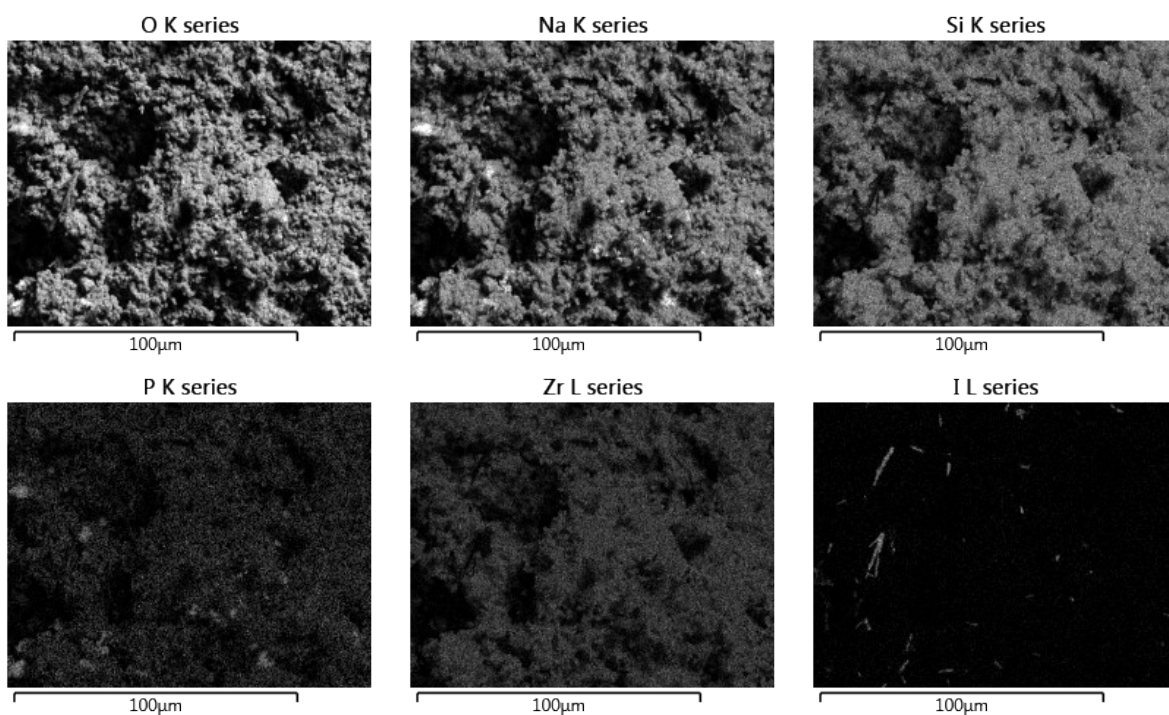
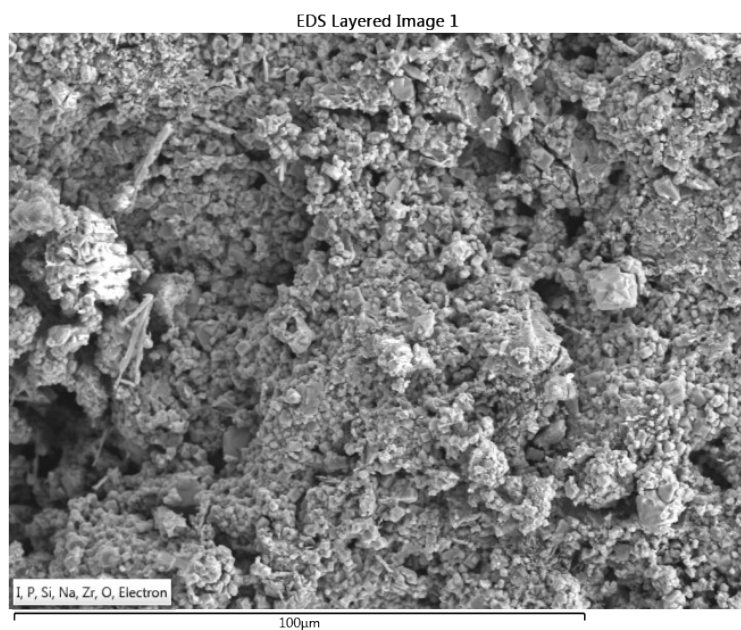


Figure S8: EDS images of sintered NaSICON powder after 10 days of exposure to 3M NaI_3 solution.

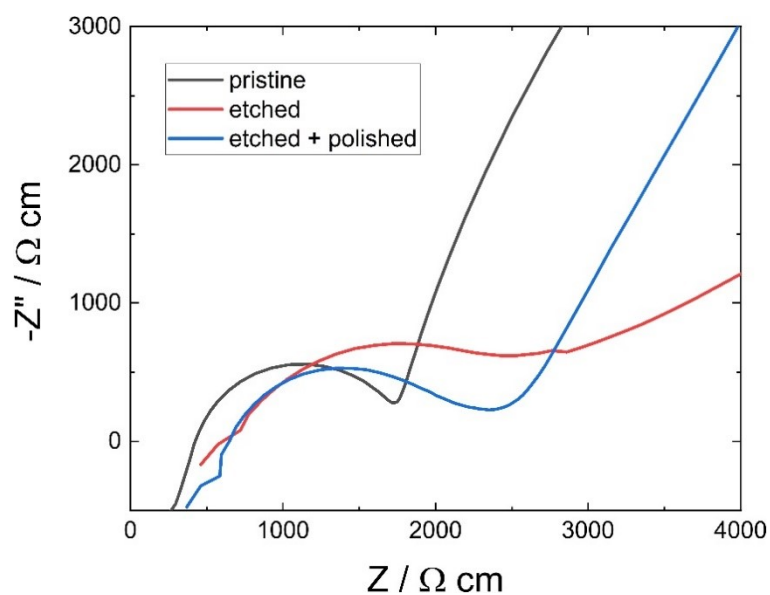


Figure S9: EIS spectra of dense $\text{Na}_{3.4}\text{Sc}_{0.4}\text{Zr}_{1.6}\text{Si}_2\text{PO}_{12}$ before and after exposure to 3M NaI_3 as well as after surface polishing of the etched pellet.

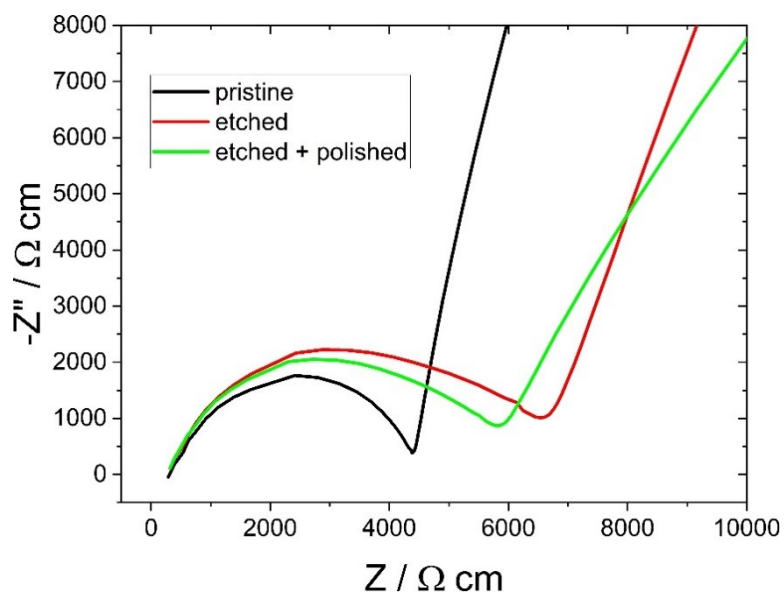


Figure S10: EIS spectra of dense $\text{Na}_{3.4}\text{Al}_{0.4}\text{Y}_{0.2}\text{Zr}_{1.6}\text{Si}_2\text{PO}_{12}$ before and after exposure to 3M NaI_3 as well as after surface polishing of the etched pellet.

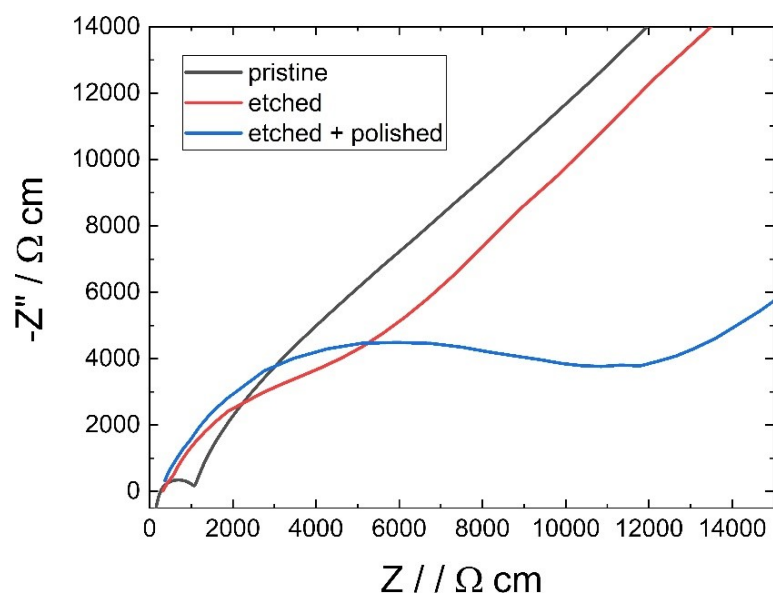


Figure S11: EIS spectra of dense $\text{Na}_{3.4}\text{Zr}_{2.4}\text{Si}_2\text{P}_{0.6}\text{O}_{12}$ before and after exposure to 3M NaI_3 as well as after surface polishing of the etched pellet.